

Supporting Information

# Electrically Erasable Multi-Level Charge Trapping Memory with Metal Nanoparticle Engineering for Organic Synaptic Transistors

*Yujeong Hwang,<sup>†</sup> Yeon-Woo Lee,<sup>‡</sup> Chang-Hyun Kim,<sup>||</sup> Hea-Lim Park,<sup>‡, \*</sup> and Min-Hoi Kim<sup>†, \*</sup>*

<sup>†</sup> Department of Creative Convergence Engineering, Hanbat National University, Daejeon 34158,

Republic of Korea

<sup>‡</sup> Department of Materials Science and Engineering, Seoul National University of Science and

Technology, Seoul 01811, Republic of Korea

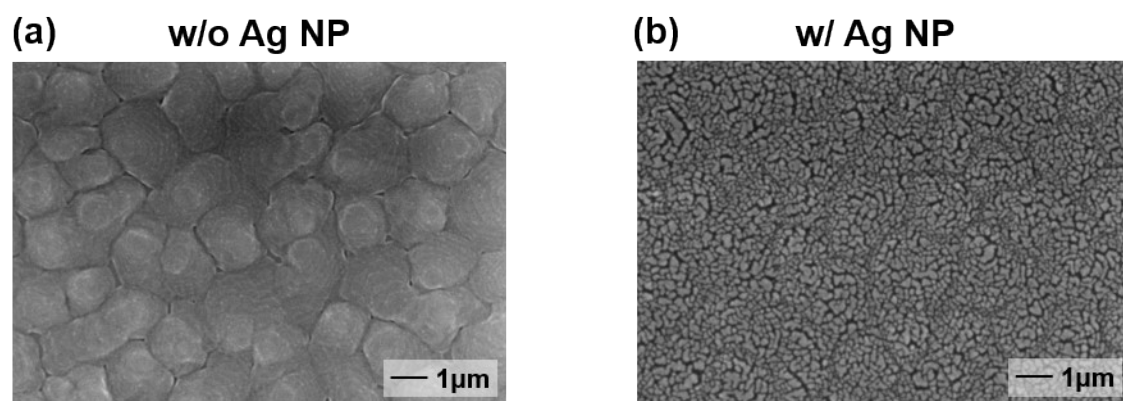
<sup>||</sup> School of Electrical Engineering and Computer Science, University of Ottawa, Ottawa, ON

K1N 6N5, Canada

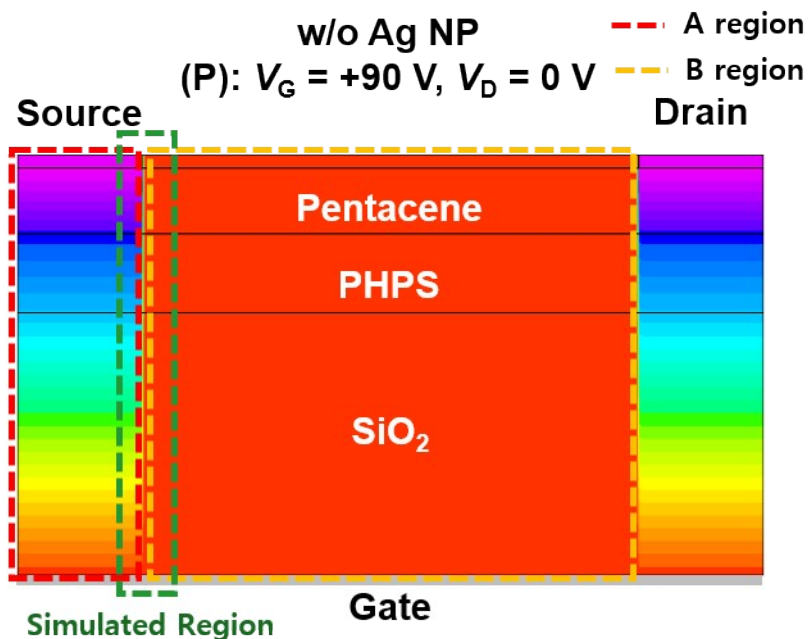
Corresponding Author

\*Email: parkhl21@seoultech.ac.kr (H.-L. Park), mhkim8@hanbat.ac.kr (M.-H. Kim).

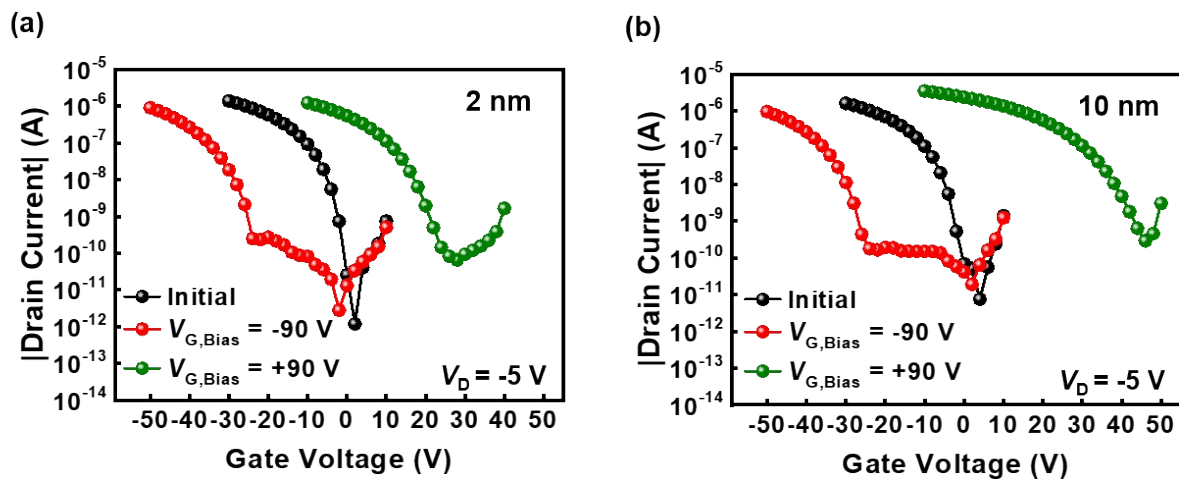
## SUPPLEMENTARY FIGURES



**Figure S1.** Scanning electron microscopy images of the surface morphology of (a) pentacene and (b) 5-nm-thick Ag NPs deposited on pentacene.

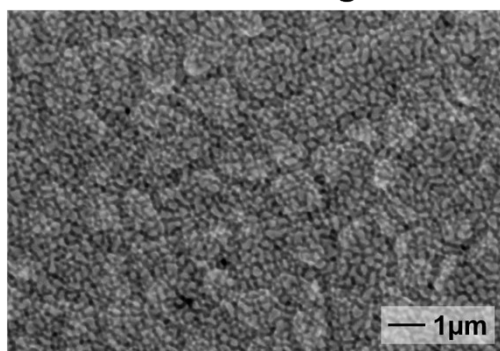


**Figure S2.** Numerical simulation of the electrical potential distribution of the entire device without Ag NPs under an erasing voltage ( $V_{G, \text{Bias}} = +90$  V). Region A indicates the region where the S/D and gate electrode overlap (red dotted line), while region B indicates the region where the gate electrode overlaps the channel without overlapping the S/D. For Fig. 2c, the simulations were performed on a portion of the source electrode and in a 200-nm-wide region near the source electrodes (green dotted box).

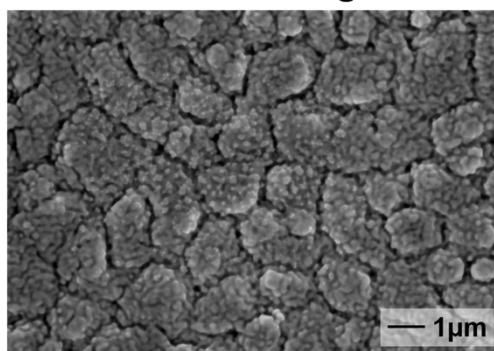


**Figure S3.** Transfer curves of devices incorporating (a) 2-nm- and (b) 10-nm-thick Ag NPs after the writing (red lines) and erasing (green lines) processes. The black lines represent the initial transfer curves of both devices.

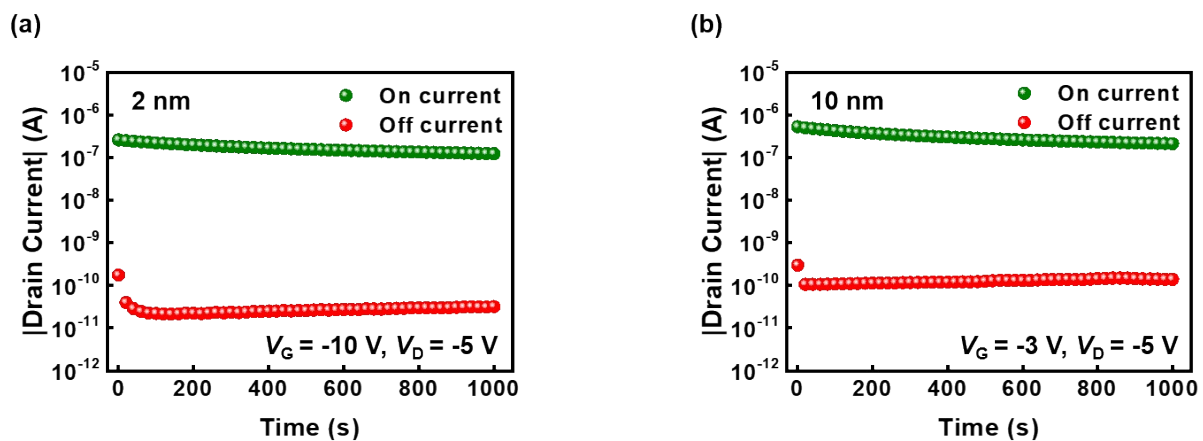
**(a) 10-nm-thick Ag NP**



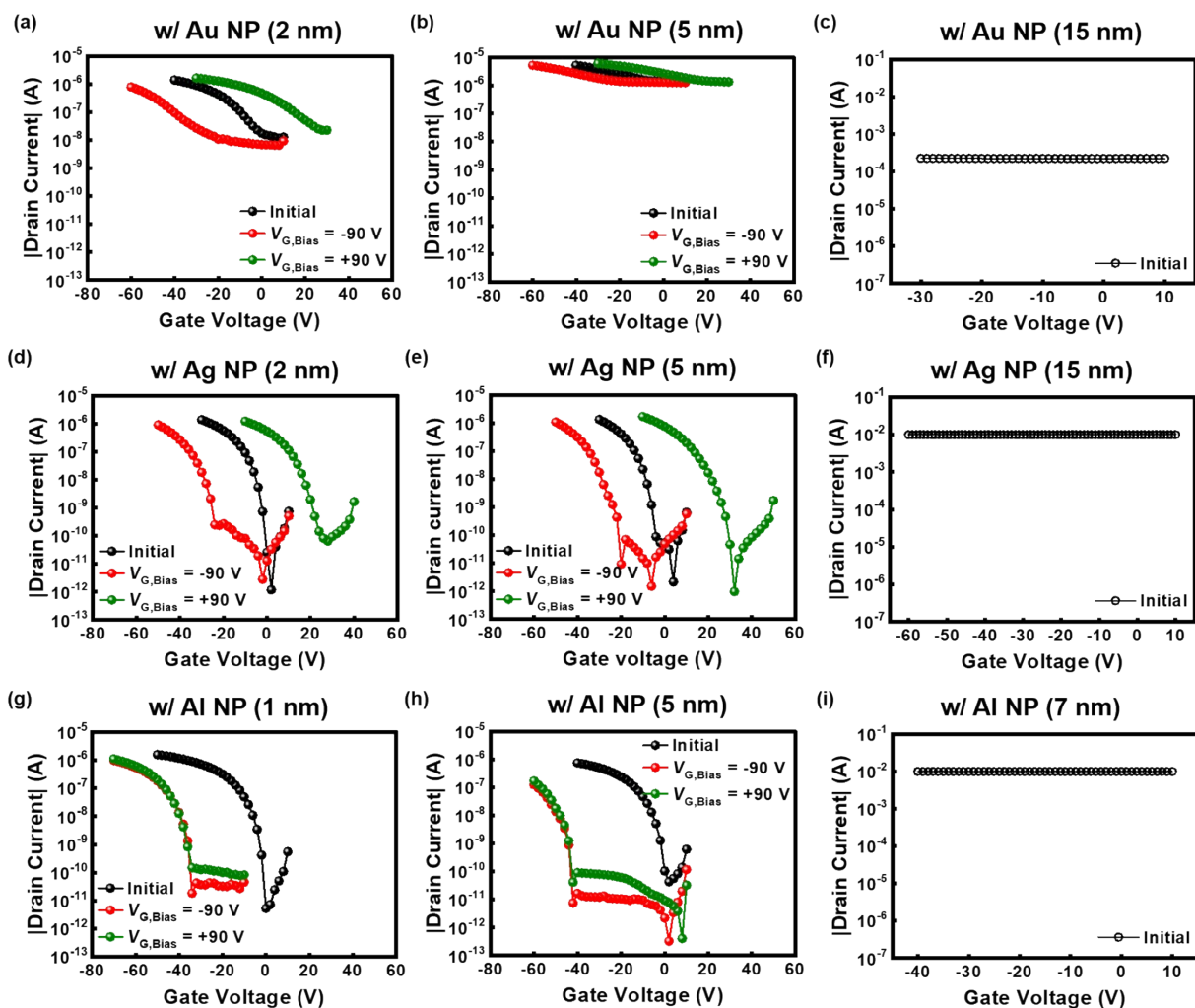
**(b) 15-nm-thick Ag NP**



**Figure S4.** Scanning electron microscopy images of the surface morphology of (a) 10-nm-thick and (b) 15-nm-thick Ag NPs deposited on pentacene.



**Figure S5.** The retention characteristics of OSTs with (a) 2-nm and (b) 10-nm thick Ag NPs.



**Figure S6.** Electrical characteristics of NP-based OSTs with three different metal electrodes (Au, Ag, and Al) as a function of deposition thickness after the writing (depression) and erasing (potentiation) processes.

Materials (Gate/Gate insulator/ CTL <sup>a</sup> / semiconductor/SD <sup>b</sup> )						Table S1.
Memory window [V]						Co
Number of states (potentiation / depression)						mpa
Conductance ratio ( $G_{\max}/G_{\min}$ )						riso
Energy consumption [J]						n of
[Ref]						olig
Ag/Al <sub>2</sub> O <sub>3</sub> / C60/PMMA hybrid layer/ Pentacene/Au						ome
~ 0.7						ric
10 / 10						syna
~ 1.2						ptic
~ $1.4 \times 10^{-7}$						tran
[1]						sisto
Substrate/ITO/Al <sub>2</sub> O <sub>3</sub> / PVPy <sup>c</sup> @MOF <sup>d</sup> / Pentacene/Au						
~ 1.5						
20 / 20						
~ 3						
~ $0.6 \times 10^{-7}$						
[2]						
Si/SiO <sub>2</sub> / BP <sup>e</sup> -ZnO hybrid NP/ Pentacene/Au						
~ 10						
25 / 25						
~ 1.4						
~ $1.8 \times 10^{-6}$						
[3]						
Si/SiO <sub>2</sub> / Polyimide/ Pentacene/Au						
84						
-						
-						
-						
[4] <sup>f</sup>						
Si/SiO <sub>2</sub> / PHPS <sup>g</sup> / pentacene/Au						
54 (Max 64 <sup>h</sup> )						
30 / 30						
~ 6						
~ $7.5 \times 10^{-9}$						
This work						

rs exhibiting potentiation/depression characteristics solely controlled by electrical pulses.



<sup>a</sup>CTL: charge trapping layer; <sup>b</sup>SD: source and drain electrodes; <sup>c</sup>PVPy: polyvinyl pyrrolidone; <sup>d</sup>MOF: metal–organic frameworks of Zn-TCPP (TCPP: tetrakis(4-carboxyphenyl)porphyrin); <sup>e</sup>BP: black phosphorus; <sup>f</sup>The demonstrated device was originally designed as a memory device rather than a synaptic transistor; therefore, data on potentiation and depression characteristics were not obtained, and energy consumption related to synaptic operation could not be evaluated; <sup>g</sup>PHPS: perhydropolysilazane; <sup>h</sup>The device with a 10-nm-thick Ag nanoparticle layer exhibited a maximum memory window of 64 V.

## References

- [1] Gate-Tunable Synaptic Plasticity through Controlled Polarity of Charge Trapping in Fullerene Composites, *Adv. Funct. Mater.* 28, 1805599 (2018)
- [2] Synaptic Plasticity and Filtering Emulated in Metal–Organic Frameworks Nanosheets Based Transistors, *Adv. Electron. Mater.* 6, 1900978 (2020)
- [3] Artificial Synapses Emulated Through a Light Mediated Organic–Inorganic Hybrid Transistor, *J. Mater. Chem. C*, 7, 48-59 (2019)
- [4] Nonvolatile Transistor Memory Devices Using High Dielectric Constant Polyimide Electrets, *J. Mater. Chem. C*, 1, 3235 (2013)